

ABSTRACT

Provided are a deposit removal method and a film
deposition method capable of removing a selenium-containing
5 deposit adhering to an inner surface of a chamber or an inner
surface of piping connected to the chamber without
disassembling the chamber. A selenium-containing deposit
adhering to at least one of the inner surface of a chamber
(10) or the inner surface of exhaust piping (15) connected
10 to the chamber (10) is removed by reacting with a cleaning
gas containing a hydrogen-containing compound gas.

Fig.1